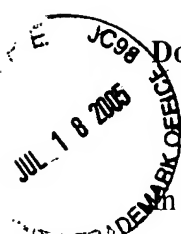


IFW



Docket No.: 4425-320

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Chien-Hsin LAI et al.

U.S. Patent Application No. 10/659,258

Filed: September 11, 2003

For: PLASMA APPARATUS AND METHOD CAPABLE OF ADAPTIVE IMPEDANCE MATCHING

:  
:  
: Confirmation No.3535  
:  
: Group Art Unit: 1763  
:  
: Examiner: KARLA A MOORE

RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

By Official Action mailed June 16, 2005, restriction to one of the following inventions is required:

Group I - Claims 1-19, drawn to an apparatus capable of adaptive impedance matching.

Group II - Claims 20-21, drawn to a method of impedance matching for a plasma apparatus.

In response, Applicants hereby elect claims 1-19.

The election was made *with traverse* because the Examiner has failed to demonstrate why the hypothetical process mentioned in paragraph 2 can be regarded as a *materially* different process. Applicants are, therefore, not persuaded that a proper Restriction Requirement has been set forth.

Early examination on the merits is courteously solicited.

To the extent necessary, a petition for an extension of time under 37 C.F.R. 1.136 is hereby made. Please charge any shortage in fees due in connection with the filing of this paper, including

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extension of time fees, to Deposit Account 07-1337 and please credit any excess fees to such deposit account.

Respectfully submitted,  
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**Date: July 18, 2005**